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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Application Number	09 / 898,521
Filing Date	July 3, 2001
First Named Inventor	Charles D. SCHAPER
Group Art Unit	
Examiner Name	

Attorney Docket Number STAN MXL 001

OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS

Examiner Initials	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
SPCh		Stephen CHOU, Peter KRAUSS, & Preston RENSTROM. "Imprint Lithography with 25-Nanometer Resolution", Science Vol. 272, April 5, 1996 pp. 85-87, USA.	
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Examiner Signature	Mohamedulla	Date Considered	8/9/04
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